



IPW

Docket No.: V9661.0056

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Jun Wang et al.

Application No.: 10/787,169

Confirmation No.: 4887

Filed: February 27, 2004

Art Unit: 1756

For: MULTIPLE EXPOSURE METHOD FOR
CIRCUIT PERFORMANCE IMPROVEMENT

Examiner: B. L. Raymond

RESPONSE TO RESTRICTION REQUIREMENT

MS Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the restriction requirement set forth in the Office Action mailed January 8, 2007 (Paper No. 20070104-A), Applicants hereby provisionally elect Group I (claims 1-15 and 21-32) for continued examination.

Because claims 21-32 also cover the method of imaging features onto a wafer, Applicants have including claims 21-32 in Group I for continued prosecution.

Applicants note that the Restriction Requirement failed to address claims 21-32. In an Examiner's interview conducted February 7, 2007, the examiner agreed that claims 21-32 should have been classified in Group I.

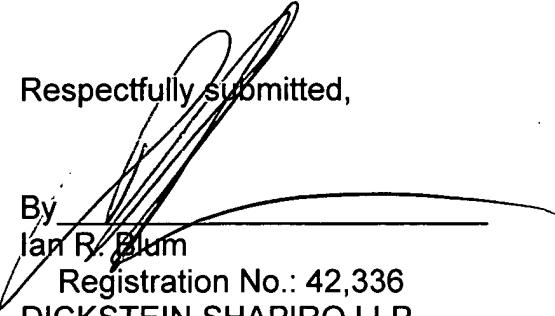
Application No.: 10/787,169

Docket No.: V9661.0056

Dated: February 8, 2007

Respectfully submitted,

By


Ian R. Blum

Registration No.: 42,336
DICKSTEIN SHAPIRO LLP
1177 Avenue of the Americas
New York, New York 10036-2714
(212) 277-6500
Attorney for Applicant

IRB/mgs